



The Fine Line : VIDEOS FOR THE EBEAM COMMUNITY

Autumn 2013

Shot Talk - A Word from our Sponsor

Aki Fujimura, CEO of D2S, recaps the hottest trends at BACUS, including breaking news, compelling papers, panel discussions, and highlights of the annual eBeam Initiative members meeting and survey results.



From the White Board

In his third and final installment on Photomask Processing and Modeling, Ryan Pearman proves the age-old adage that the whole is greater than the sum of its parts as he analyzes the makeup of a production-worthy single Gaussian resist process model.



Tech Talk

Dr. Kokoro Kato of Hitachi High-Tech Science Corp. outlines new GPU-based verification methods for overlapping shots that are significantly faster and consume less power than conventional CPU methods.



Perspectives

Industry luminary Brian Grenon discusses what surprised him most about results of the eBeam Initiative survey presented at BACUS, including sentiment on multi-beam for mask and wafer writing, mask write times at the 10-nm node, and prospects for larger mask sizes.



VIDEO ARCHIVE

The Fine Line Spring Edition



Shot Talk: Aki Fujimura of D2S



From the White Board:
Ryan Pearman



Tech Talk: Mike Smayling of
Tela Innovations



Perspectives: Tatsuhiko
Higashiki of Toshiba

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The eBeam Initiative is a forum dedicated to the education and promotion of new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeam.org or visit www.ebeam.org